L Number	Hits	Search Text	DB	Time stamp
ī	514	'ta.sub.2 o.sub.5' with 'la.sub.2 o.sub.3'	USPAT	2003/01/26
1	, ,,,	Edition 2 clouds 3 With Micros 2 clouds		14:59
2	0	('ta.sub.2 o.sub.5' with 'la.sub.2 o.sub.3') with beta	USPAT	2003/01/26
4	U	( ta.3db.2 0.3db.3 With la.3db.2 0.3db.3 ) With beta	001711	14:35
3	0	('ta.sub.2 o.sub.5' with 'la.sub.2 o.sub.3') with 'beta'	USPAT	2003/01/26
		( ta.sub.2 o.sub.5 With ta.sub.2 o.sub.5 ) With beta	Corni	14:36
4	254	('ta.sub.2 o.sub.5' with 'la.sub.2 o.sub.3') and coating	USPAT	2003/01/26
-	251	(ta.sub.2 o.sub.5 with ta.sub.2 o.sub.5 ) and coating	001111	14:36
5	229	('ta.sub.2 o.sub.5' with 'la.sub.2 o.sub.3') and silicon	USPAT	2003/01/26
	223	( talsub.2 oloubly with talsub.2 oloubly and oldeon	001111	14:36
6	132523	428/\$.ccls.	USPAT	2003/01/26
	.52525	130,4,403		14:36
7	87	428/\$.ccls. and ('ta.sub.2 o.sub.5' with 'la.sub.2 o.sub.3')	USPAT	2003/01/26
'		, <del>, , , , , , , , , , , , , , , , , , </del>		14:44
8	68	(tantalum with lanthanum with oxide) and 428/\$.ccls.	USPAT	2003/01/26
"		(**************************************		14:45
9	63	((tantalum with lanthanum with oxide) and 428/\$.ccls.) and silicon	USPAT	2003/01/26
	O J	((		14:54
10	15	'tantalum pentoxide' with ('lanthanum oxide' or 'la.sub.2 o.sub.3')	USPAT	2003/01/26
•				14:55
111	57	'ta.sub.2 o.sub.5' with 'lanthanum oxide'	USPAT	2003/01/26
				15:13
12	0	'ta2o3' with 'lanthanum oxide'	EPO; JPO;	2003/01/26
			DERWENT	15:08
13	5	'ta2o5' with 'lanthanum oxide'	EPO; JPO;	2003/01/26
			DERWENT	15:10
14	21	'tantalum oxide' with 'lanthanum oxide'	EPO; JPO;	2003/01/26
			DERWENT	15:09
15	9	('tantalum oxide' with 'lanthanum oxide') and silicon	EPO; JPO;	2003/01/26
			DERWENT	15:10
16	0	('tantalum oxide' with 'lanthanum oxide') and 'Sic'	EPO; JPO;	2003/01/26
			DERWENT	15:10
17	0	('tantalum oxide' with 'lanthanum oxide') and 'SiN'	EPO; JPO;	2003/01/26
			DERWENT	15:10
18	396	"ta2o5" with "la2o3"	EPO; JPO;	2003/01/26
i l			DERWENT	15:10
19	74	('ta2o5' with 'la2o3') and silicon	EPO; JPO;	2003/01/26
			DERWENT	15:10
20	1	(('ta2o5' with 'la2o3') and silicon) and coating	EPO; JPO;	2003/01/26 15:11
			DERWENT	
21	6	(('ta2o5' with 'la2o3') and silicon) and layer	EPO; JPO;	2003/01/26
		(1, 2, 5), (1, 1, 2, 3), (1, 1, 2, 3)	DERWENT	15:12
22	16	('ta205' with 'la203') and SiC	EPO; JPO;	2003/01/26
		(to 2-5) (ch th-2-2) (co 15)	DERWENT	15:12
23	1	('ta205' with 'la203') and SiN	EPO; JPO;	2003/01/26
34	430	to	DERWENT	15:12
24	438	'tantalum pentoxide'	EPO; JPO;	2003/01/26
125		transalum nontovidal and (lanthonym and de and 1-2021)	DERWENT	15:13
25	2	'tantalum pentoxide' and ('lanthanum oxide' or 'la203')	EPO; JPO; DERWENT	2003/01/26
1 26	200124	'ta.sub.2 o.sub.5' with 'lanthanum oxide' amd silicon	USPAT	15:13
26	298124	ta.sub.2 o.sub.3 with Tanthahum oxide amd sincon	USFAI	2003/01/26 15:14
27	298124	('ta.sub.2 o.sub.5' with 'lanthanum oxide') amd silicon	USPAT	2003/01/26
41	290124	( ta.sub.2 0.sub.) With fanthalium oxide ) amd sincon	USIAI	15:14
28	46	('ta.sub.2 o.sub.5' with 'lanthanum oxide') and silicon	USPAT	2003/01/26
20	10	( ca.sao.2 o.sao.5 with fatitulation oxide ) and sincon	COLAT	15:14
L		L		13.11